PRISM News

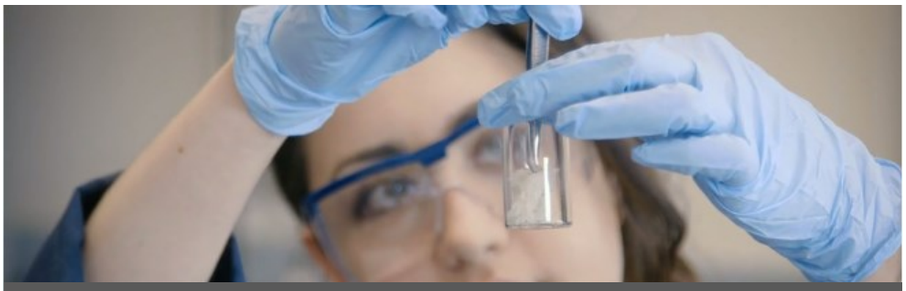
PRINCETON INSTITUTE FOR THE SCIENCE AND TECHNOLOGY OF MATERIALS

SEPTEMBER 2016

MESSAGE FROM THE DIRECTOR

Welcome to the new semester, I hope everyone had a great summer. We're almost done with the relocation of our IAC and MNFL so swing by and check out some of our new equipment and expanded capabilities. Please mark your calendars for our special inauguration event and our annual blacksmithing day next month and stay tuned for more great things to come!

NEWS



Undergraduates get research experience in leading labs

Craig Arnold: Perspective on the allure and reach of materials science

FACULTY HIGHLIGHT

faculty highlight

Please welcome our newest faculty members to PRISM!

Ian Bourg
Assistant Professor of Civil and Environmental Engineering and the Princeton Environmental Institute

The Bourg group is examines the geochemical and mass transport properties of porous media, READ MORE

Nathalie de Leon
Assistant Professor of Electrical Engineering

The de Leon group is focused on building quantum hardware with color centers in wide bandgap materials, READ MORE

Andrej Kosmrlj
Assistant Professor of Mechanical Aerospace and Engineering

Prof. Kosmrlj's principal research efforts are materials and mechanical systems, READ MORE

Jeff Thompson
Assistant Professor of Electrical Engineering

Prof. Thompson's research explores methods to gain control over individual atoms for computing, READ MORE

PRISM | PCCM SEMINAR SERIES

September 21
Florian Müller-Plathe
Technische Universität Darmstadt

September 28
Chunlei Guo
University of Rochester

October 5
Zahra Fakhraai
University of Pennsylvania

For a complete schedule, go to www.princeton.edu/prism

SAVE-THE-DATE

OCTOBER 8, 2016
Man of Steel, a Blacksmithing and Metallurgy Event

OCTOBER 26, 2016
PRISM Micro/Nano Fabrication Lab (MNFL) & Imaging and Analysis Center (IAC) Inauguration

NEW EQUIPMENT IN THE MNFL

Heidelberg DWL 66$^+$ Laser Lithography Tool

The Heidelberg instrument DWL 66$^+$ laser based lithography exposure tool is used to direct write pattern photomasks and substrates of various types and sizes. This tool is capable of front-to-back substrate alignment and a number of exposure modes including raster, vector and 3D (gray scale) to produce complex pattern geometries and topography.

PRINCETON UNIVERSITY